

*“Modeling of the target surface modification by reactive ion implantation during magnetron sputtering”*. Depla D, Chen ZY, Bogaerts A, Ignatova V, de Gryse R, Gijbels R, Journal of vacuum science and technology: A: vacuum surfaces and films **22**, 1524 (2004).  
<http://doi.org/10.1116/1.1705641>